

GP 1765

Patent  
Attorney's Docket No. 015290-238

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

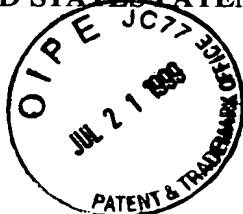
In re Patent Application of

Jeffrey HUNG et al.

Application No.: 09/002,007

Filed: December 31, 1997

For: ETCHING PROCESS FOR ORGANIC  
ANTI-REFLECTIVE COATING



) Group Art Unit: 1765

) Examiner: L. Vinh

REPLY TRANSMITTAL LETTER

Assistant Commissioner for Patents  
Washington, D.C. 20231

Sir:

Enclosed is a reply for the above-identified patent application.

☐ A Petition for Extension of Time is also enclosed.

☐ Also enclosed is \_\_\_\_\_

☐ \_\_\_\_\_ statement(s) claiming small entity status  
☐ are also enclosed ☐ were submitted previously.

☐ A Request for Entry and Consideration of Submission under 37 C.F.R. § 1.129(a) is also enclosed.

☐ No additional claim fee is required.

☒ An additional claim fee is required, and is calculated as shown below:

RECEIVED  
JUL 23 1999  
TC 1700 MAIL ROOM

AMENDED CLAIMS					
	NO. OF CLAIMS	HIGHEST NO. OF CLAIMS PREVIOUSLY PAID FOR	EXTRA CLAIMS	RATE	ADDT'L FEE
Total Claims	21	MINUS 20 =	1	x \$18.00 =	18.00
Independent Claims	3	MINUS 3 =	0	x \$78.00 =	
If Amendment adds multiple dependent claims, add \$260.00					
Total Amendment Fee					
If small entity status is claimed, subtract 50% of Total Amendment Fee					
<b>TOTAL ADDITIONAL FEE DUE FOR THIS AMENDMENT</b>					<b>\$18.00</b>

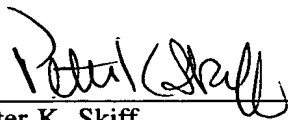
☒ A claim fee in the amount of \$ 18.00 is enclosed.

☐ Charge \$ \_\_\_\_\_ to Deposit Account No. 02-4800.

The Commissioner is hereby authorized to charge any appropriate fees under 37 C.F.R. §§ 1.16, 1.17 and 1.21 that may be required by this paper, and to credit any overpayment, to Deposit Account No. 02-4800. This paper is submitted in triplicate.

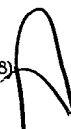
Respectfully submitted,

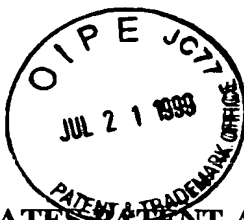
BURNS, DOANE, SWECKER & MATHIS, L.L.P.

By:   
 Peter K. Skiff  
 Registration No. 31,917

P.O. Box 1404  
 Alexandria, Virginia 22313-1404  
 (703) 836-6620

Date: July 21, 1999

(11/98) 



Patent  
Attorney's Docket No. 015290-238

#8/A  
10  
7/26/99

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of )

Jeffrey HUNG et al. )

Application No.: 09/002,007 )

Filed: December 31, 1997 )

For: ETCHING PROCESS FOR ORGANIC )  
ANTI-REFLECTIVE COATING )

Group Art Unit: 1765

Examiner: L. Vinh

RECEIVED  
JUL 23 1999  
TC 1100 MAIL ROOM

AMENDMENT

Assistant Commissioner for Patents  
Washington, D.C. 20231

Sir:

In response to the Official Action dated April 21, 1999, please amend the above-identified application as follows.

IN THE CLAIMS:

Please amend the claims and add new claims as follows:

CA1 93. (Amended) The process of Claim 1, wherein the ARC is exposed by channels forming [an interconnecting network] a circuit pattern previously etched in <sup>the</sup> a photoresist covering the ARC.

[Claim 4, line 2, change "essential" to --essentially--.]

A2 10. (Amended) The process of Claim 1, wherein the plasma is generated adjacent a substrate including the ARC, the plasma generating device including a dielectric window facing the substrate and [generating device includes] an antenna outside the reaction

12

A